

Electrostatically Actuated Cantilever

Introduction

The elastic cantilever beam is an elementary structure in MEMS design. This example shows the bending of a beam due to electrostatic forces. The model uses the electromechanics multiphysics interface to solve the coupled equations for the structural deformation and the electric field. Such structures are frequently tested by means of a low frequency capacitance voltage sweep. The model predicts the results of such a test.

Model Definition

Figure 1 shows the model geometry. The beam has the following dimensions:

- Length: 300 μm
- Width: 20 μm
- Thickness 2 µm

Because the geometry is symmetric, only half of the beam needs to modeled. The beam is made of polysilicon with a Young's modulus, E, of 153 GPa, and a Poisson's ratio, v, of 0.23. It is fixed at one end but is otherwise free to move. The polysilicon is assumed to be heavily doped, so that electric field penetration into the structure can be neglected. In this case, the Domain Terminal feature can be used to set up the Si domain. The beam resides in an air-filled chamber that is electrically insulated. The lower side of the chamber has a grounded electrode.

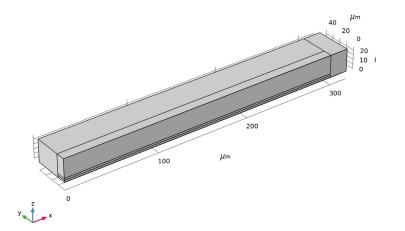


Figure 1: Model Geometry. The beam is 300 μ m long and 2 μ m thick, and it is fixed at x = 0. The model uses symmetry on the zx-plane at y = 0. The lower boundary of the surrounding air domain represents the grounded substrate. The model has 20 μ m of free air above and to the sides of the beam, while the gap below the beam is 2 μ m.

An electrostatic force caused by an applied potential difference between the two electrodes bends the beam toward the grounded plane beneath it. To compute the electrostatic force, this example calculates the electric field in the surrounding air. The model considers a layer of air 20 μ m thick both above and to the sides of the beam, and the air gap between the bottom of the beam and the grounded layer is initially 2 μ m. As the beam bends, the geometry of the air gap changes continuously, resulting in a change in the electric field between the electrodes. The coupled physics is handled automatically by the Electromechanics multiphysics interface.

The electrostatic field in the air and in the beam is governed by Poisson's equation:

$$-\nabla \cdot (\varepsilon \nabla V) = 0$$

where derivatives are taken with respect to the spatial coordinates. The numerical model represents the electric potential and its derivatives on a mesh which is moving with respect to the spatial frame. The necessary transformations are taken care of by the Electromechanics multiphysics interface, which also contains smoothing equations governing the movement of the mesh in the air domain.

The cantilever connects to a voltage terminal with a specified bias potential, V_{in} . The bottom of the chamber is grounded, while all other boundaries are electrically insulated. The terminal boundary condition automatically computes the capacitance of the system.

The force density that acts on the electrode of the beam results from Maxwell's stress tensor:

$$\mathbf{F}_{es} = -\frac{1}{2}(\mathbf{E} \cdot \mathbf{D})\mathbf{n} + (\mathbf{n} \cdot \mathbf{E})\mathbf{D}$$

where **E** and **D** are the electric field and electric displacement vectors, respectively, and **n** is the outward normal vector of the boundary. This force is always oriented along the normal of the boundary.

Navier's equations, which govern the deformation of a solid, are more conveniently written in a coordinate system that follows and deforms with the material. In this case, these reference or material coordinates are identical to the actual mesh coordinates.

Results and Discussion

There is positive feedback between the electrostatic forces and the deformation of the cantilever beam. The forces bend the beam and thereby reduce the gap to the grounded substrate. This action, in turn, increases the forces. At a certain voltage the electrostatic forces overcome the stress forces, the system becomes unstable, and the gap collapses. This critical voltage is called the *pull-in voltage*.

At applied voltages lower than the pull-in voltage, the beam stays in an equilibrium position where the stress forces balance the electrostatic forces. Figure 2 shows the beam displacement and the corresponding displacement of the mesh surrounding it. Figure 3 shows the electric potential and electric field that generates these displacements. In Figure 4 the shape of the cantilever's deflection is illustrated for each applied voltage, by plotting the z-displacement of the underside of the beam at the symmetry boundary. The tip deflection as a function of applied voltage is shown in Figure 5. Note that for applied voltages higher than the pull-in voltage, the solution does not converge because no stable stationary solution exists. This situation occurs if an applied voltage of 6.2 V is tried. The pull-in voltage is therefore between 6.1 V and 6.2 V. For comparison, computations in Ref. 1 predict a pull-in voltage of

$$V_{\rm PI} = \sqrt{\frac{4c_1B}{\varepsilon_0 L^4 c_2^2 \left(1 + c_3 \frac{g_0}{W}\right)}}$$

where $c_1 = 0.07$, $c_2 = 1.00$, and $c_3 = 0.42$; g_0 is the initial gap between the beam and the ground plane; and

$$\hat{B} = EH^3g_0^3$$

If the beam has a narrow width (W) relative to its thickness (H) and length (L), \hat{E} is Young's modulus, E. Otherwise, E and \hat{E} , the plate modulus, are related by

$$\frac{E}{E} \approx 1 - v^2 \left(\frac{(W/L)^{1.37}}{0.5 + (W/L)^{1.37}}\right)^{0.98(L/H)^{-0.056}}$$

where v is Poisson's ratio. Because the calculation in Ref. 1 uses a parallel-plate approximation for calculating the electrostatic force and because it corrects for fringing fields, these results are not directly comparable with those from the simulation. However the agreement is still reasonable: setting $W = 20 \,\mu\text{m}$ results in $V_{PI} = 6.07 \,\text{V}$.

V0(8)=6.1 V Surface: Displacement field, Z component (µm) Slice: Spatial mesh displacement z (µm)

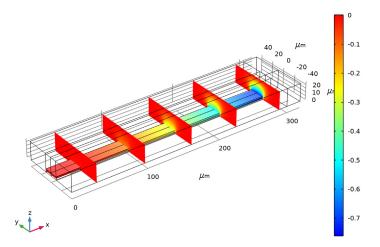
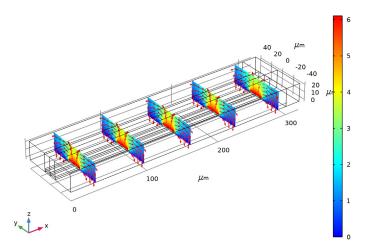


Figure 2: z-displacement for the beam and the moving mesh as a function of position. Each mesh element is depicted as a separate block in the back half of the geometry.



V0(8)=6.1 V Multislice: Electric potential (V) Arrow Volume: Electric field (spatial frame)

Figure 3: Electric Potential (color) and Electric Field (arrows) at various cross sections through the beam.

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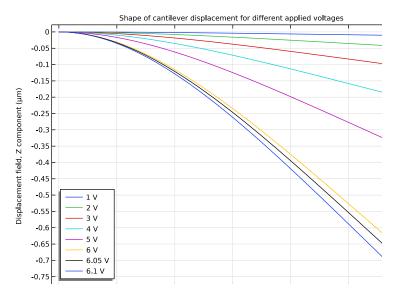


Figure 4: Displacement of the lower surface of the cantilever, plotted along the symmetry boundary, for different values of the applied voltage.

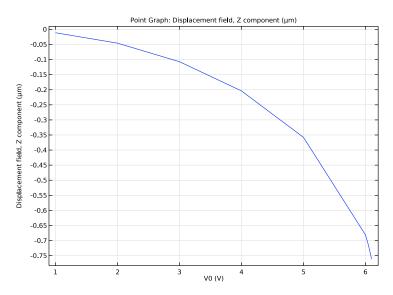


Figure 5: Cantilever tip displacements as a function of applied Voltage V_0 .

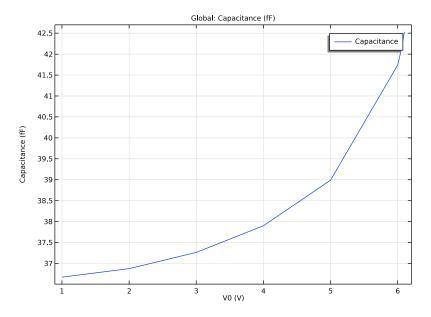


Figure 6: Device capacitance vs applied voltage V_0 .

Figure 6 shows the DC C-V curve predicted for the cantilever beam. To some extent, this is consistent with the behavior of an ideal parallel plate capacitor, whose capacitance increases with decreasing distance between the plates. But this effect does not account for all the change in capacitance observed. In fact, most of it is due to the gradual softening of the coupled electromechanical system. This effect leads to a larger structural response for a given voltage increment at higher bias, which in turn means that more charge must be added to retain the voltage difference between the electrodes.

Reference

1. R.K. Gupta, *Electrostatic Pull-In Structure Design for In-Situ Mechanical Property Measurements of Microelectromechanical Systems (MEMS)*, Ph.D. thesis, MIT, 1997.

Application Library path: MEMS_Module/Actuators/ electrostatically_actuated_cantilever

Modeling Instructions

From the File menu, choose New.

NEW

In the New window, click 🙆 Model Wizard.

MODEL WIZARD

- I In the Model Wizard window, click 间 3D.
- 2 In the Select Physics tree, select Structural Mechanics>Electromagnetics-Structure Interaction>Electromechanics>Electromechanics.
- 3 Click Add.
- 4 Click 🔿 Study.
- 5 In the Select Study tree, select General Studies>Stationary.
- 6 Click **M** Done.

GEOMETRY I

Use microns to define the geometry units.

- I In the Model Builder window, under Component I (compl) click Geometry I.
- 2 In the Settings window for Geometry, locate the Units section.
- **3** From the **Length unit** list, choose **µm**.

Create two blocks to represent the cantilever and air domains, respectively.

Block I (blkI)

- I In the **Geometry** toolbar, click **[]** Block.
- 2 In the Settings window for Block, locate the Size and Shape section.
- 3 In the Width text field, type 300.
- 4 In the **Depth** text field, type 10.
- 5 In the Height text field, type 2.
- 6 Locate the Position section. In the z text field, type 2.

7 Click 틤 Build Selected.

Block 2 (blk2)

- I In the **Geometry** toolbar, click **[]** Block.
- 2 In the Settings window for Block, locate the Size and Shape section.
- 3 In the Width text field, type 320.

- 4 In the **Depth** text field, type 40.
- 5 In the Height text field, type 24.

Add two more blocks to simplify meshing of the geometry.

Block 3 (blk3)

- I In the **Geometry** toolbar, click 🗍 **Block**.
- 2 In the Settings window for Block, locate the Size and Shape section.
- 3 In the Width text field, type 20.
- 4 In the **Depth** text field, type 40.
- 5 In the Height text field, type 24.
- 6 Locate the **Position** section. In the **x** text field, type 300.

Block 4 (blk4)

- I In the **Geometry** toolbar, click 🗍 **Block**.
- 2 In the Settings window for Block, locate the Size and Shape section.
- 3 In the Width text field, type 300.
- 4 In the **Depth** text field, type 10.
- 5 In the **Height** text field, type 24.
- 6 Click 📗 Build All Objects.

Add a parameter for the DC voltage applied to the cantilever.

GLOBAL DEFINITIONS

Parameters 1

- I In the Model Builder window, under Global Definitions click Parameters I.
- 2 In the Settings window for Parameters, locate the Parameters section.
- **3** In the table, enter the following settings:

Name	Expression	Value	Description
V0	5[V]	5 V	Bias on cantilever

The cantilever is assumed to be heavily doped so that it acts as a conductor, held at constant potential. The **Linear Elastic Material** feature is therefore used.

SOLID MECHANICS (SOLID)

I In the Model Builder window, under Component I (compl) click Solid Mechanics (solid).

2 Select Domain 2 only.

ELECTROSTATICS (ES)

The default **Charge Conservation** feature was set to use solid material type. Add one more feature to represent the nonsolid (air) domains.

I In the Model Builder window, under Component I (compl) click Electrostatics (es).

Charge Conservation, Air

- I In the Physics toolbar, click 📄 Domains and choose Charge Conservation.
- 2 In the Settings window for Charge Conservation, type Charge Conservation, Air in the Label text field.
- **3** Select Domains 1 and 3–5 only.
- **4** Locate the **Domain Selection** section. Click **Create Selection**.
- 5 In the Create Selection dialog box, type Air in the Selection name text field.
- 6 Click OK.

DEFINITIONS

Deforming Domain I

- I In the Model Builder window, under Component I (compl)>Definitions>Moving Mesh click Deforming Domain I.
- 2 In the Settings window for Deforming Domain, locate the Domain Selection section.
- 3 From the Selection list, choose Air.

Fix one end of the cantilever.

SOLID MECHANICS (SOLID)

In the Model Builder window, under Component I (compl) click Solid Mechanics (solid).

Fixed Constraint 1

- I In the Physics toolbar, click 🔚 Boundaries and choose Fixed Constraint.
- 2 Select Boundary 4 only.

Since only half of the cantilever is included in the model, the symmetry condition should be applied on the midplane of the solid. The electric field default condition (**Zero Charge**) is equivalent to a symmetry condition, so only the structural symmetry boundary condition needs to be applied.

Symmetry I

- I In the Physics toolbar, click 🔚 Boundaries and choose Symmetry.
- **2** Select Boundary 5 only.

DEFINITIONS

Symmetry/Roller 1

- I In the Model Builder window, under Component I (compl)>Definitions>Moving Mesh click Symmetry/Roller I.
- 2 Select Boundaries 2, 8, and 19 only.

Use the **Domain Terminal** feature to set the voltage of the cantilever. Note: The Domain Terminal feature will be very handy for a conducting domain with a complex shape and many exterior boundaries - instead of selecting all the boundaries to set up the Ground, Terminal, or Electric Potential boundary condition, we only need to select the domain to specify the Domain Terminal with the same effect. In addition, the computation load is reduced, because the electrostatic degrees of freedom within the Domain Terminal do not need to be solved for.

ELECTROSTATICS (ES)

In the Model Builder window, under Component I (compl) click Electrostatics (es).

Terminal I

- I In the Physics toolbar, click 🔚 Domains and choose Terminal.
- **2** Select Domain 2 only.
- 3 In the Settings window for Terminal, locate the Terminal section.
- 4 From the Terminal type list, choose Voltage.
- **5** In the V_0 text field, type V0.

Set up the ground plane underneath the cantilever.

Ground I

- I In the Physics toolbar, click 📄 Boundaries and choose Ground.
- **2** Select Boundaries 3 and 13 only.

Add Materials to the model.

MATERIALS

Material I (mat1)

- I In the Model Builder window, under Component I (compl) right-click Materials and choose Blank Material.
- 2 In the Settings window for Material, locate the Geometric Entity Selection section.
- 3 From the Selection list, choose Air.

4 Locate the **Material Contents** section. In the table, enter the following settings:

Property	Variable	Value	Unit	Property group
Relative permittivity	epsilonr_iso ; epsilonrii = epsilonr_iso, epsilonrij = 0	1	I	Basic

Material 2 (mat2)

- I Right-click Materials and choose Blank Material.
- **2** Select Domain 2 only.
- 3 In the Settings window for Material, locate the Material Contents section.
- **4** In the table, enter the following settings:

Property	Variable	Value	Unit	Property group
Young's modulus	E	153[GPa]	Pa	Basic
Poisson's ratio	nu	0.23	I	Basic
Density	rho	2330	kg/m³	Basic

MESH I

Mapped I

- I In the Mesh toolbar, click \bigwedge Boundary and choose Mapped.
- **2** Select Boundaries 1, 4, and 7 only.

Distribution I

- I Right-click Mapped I and choose Distribution.
- **2** Select Edges 1, 2, 4, 5, 8, 12, and 15 only.
- 3 In the Settings window for Distribution, locate the Distribution section.
- 4 In the Number of elements text field, type 2.

Distribution 2

- I In the Model Builder window, right-click Mapped I and choose Distribution.
- 2 Select Edges 7 and 17 only.
- **3** In the Settings window for Distribution, click 📗 Build Selected.

Copy Edge 1

I In the Model Builder window, right-click Mesh I and choose More Operations>Copy Edge.

- **2** Select Edges 12, 15, and 17 only.
- 3 In the Settings window for Copy Edge, locate the Destination Edges section.
- **4** Select the **I** Activate Selection toggle button.
- 5 Select Edge 21 only.
- 6 Click 🖷 Build Selected.

Mapped 2

- I In the Mesh toolbar, click \bigwedge Boundary and choose Mapped.
- **2** Select Boundary 11 only.

Distribution I

- I Right-click Mapped 2 and choose Distribution.
- 2 Select Edges 13 and 19 only.
- 3 In the Settings window for Distribution, click 📗 Build Selected.

Swept I

In the **Mesh** toolbar, click A Swept.

Distribution I

- I Right-click Swept I and choose Distribution.
- **2** Select Domains 1–4 only.
- 3 In the Settings window for Distribution, locate the Distribution section.
- 4 In the Number of elements text field, type 15.

Distribution 2

- I In the Model Builder window, right-click Swept I and choose Distribution.
- **2** Select Domain 5 only.
- 3 In the Settings window for Distribution, locate the Distribution section.
- 4 In the Number of elements text field, type 1.
- 5 Click 📗 Build All.

Set up a **Parametric Sweep** over the applied voltage.

STUDY I

Step 1: Stationary

- I In the Model Builder window, under Study I click Step I: Stationary.
- 2 In the Settings window for Stationary, click to expand the Study Extensions section.

- 3 Select the Auxiliary sweep check box.
- 4 Click + Add.
- 5 Click Range.
- 6 In the Range dialog box, type 1 in the Start text field.
- 7 In the **Step** text field, type 1.
- 8 In the Stop text field, type 6.
- 9 Click Add.

Add points at 6.05 and 6.1 V to the sweep by adding these points after the range statement. The table field should now contain: range(1,1,6) 6.05 6.1.

IO In the **Home** toolbar, click **= Compute**.

RESULTS

Displacement (solid)

Create a mirrored dataset for postprocessing.

Mirror 3D I

- I In the **Results** toolbar, click **More Datasets** and choose **Mirror 3D**.
- 2 In the Settings window for Mirror 3D, locate the Plane Data section.
- 3 From the Plane list, choose zx-planes.

Edit the first default plot to show the *z*-displacement and the corresponding mesh deformation.

Vertical displacement (solid)

- I In the Model Builder window, under Results click Displacement (solid).
- 2 In the Settings window for 3D Plot Group, type Vertical displacement (solid) in the Label text field.
- 3 Locate the Data section. From the Dataset list, choose Mirror 3D I.

Surface 1

- I In the Model Builder window, expand the Vertical displacement (solid) node, then click Surface I.
- 2 In the Settings window for Surface, locate the Expression section.
- 3 In the Expression text field, type w.

Slice 1

I In the Model Builder window, right-click Vertical displacement (solid) and choose Slice.

- 2 In the Settings window for Slice, locate the Expression section.
- 3 In the **Expression** text field, type spatial.w.
- 4 Click to expand the Inherit Style section. From the Plot list, choose Surface I.
- 5 In the Vertical displacement (solid) toolbar, click **O** Plot.

Edit the second default potential plot.

Electric Potential (es)

- I In the Model Builder window, click Electric Potential (es).
- 2 In the Settings window for 3D Plot Group, locate the Data section.
- 3 From the Dataset list, choose Mirror 3D I.

Multislice 1

- I In the Model Builder window, expand the Electric Potential (es) node, then click Multislice I.
- 2 In the Settings window for Multislice, locate the Multiplane Data section.
- 3 Find the x-planes subsection. In the Planes text field, type 5.
- 4 Find the y-planes subsection. In the Planes text field, type 0.
- 5 Find the z-planes subsection. In the Planes text field, type 0.

Arrow Volume 1

- I In the Model Builder window, right-click Electric Potential (es) and choose Arrow Volume.
- 2 In the Settings window for Arrow Volume, click Replace Expression in the upper-right corner of the Expression section. From the menu, choose Component I (comp1)> Electrostatics>Electric>es.Ex,...,es.Ez Electric field (spatial frame).
- **3** Locate the **Arrow Positioning** section. Find the **x grid points** subsection. In the **Points** text field, type **5**.
- 4 Find the y grid points subsection. In the Points text field, type 10.
- 5 Find the z grid points subsection. In the Points text field, type 5.
- 6 Locate the Coloring and Style section. From the Arrow length list, choose Normalized.
- 7 In the Electric Potential (es) toolbar, click 🗿 Plot.

Add a plot to show the deformed shape of the underside of the cantilever.

ID Plot Group 3

In the Home toolbar, click 🚛 Add Plot Group and choose ID Plot Group.

Line Graph 1

I Right-click ID Plot Group 3 and choose Line Graph.

- 2 Select Edge 6 only.
- In the Settings window for Line Graph, click Replace Expression in the upper-right corner of the y-Axis Data section. From the menu, choose Component I (compl)>
 Solid Mechanics>Displacement>Displacement field m>w Displacement field, Z component.
- 4 Click to expand the Legends section. Select the Show legends check box.

Displacement vs. Applied Voltage

- I In the Model Builder window, click ID Plot Group 3.
- 2 In the Settings window for ID Plot Group, locate the Legend section.
- **3** From the **Position** list, choose **Lower left**.
- 4 Click to expand the Title section. From the Title type list, choose Manual.
- **5** In the **Title** text area, type Shape of cantilever displacement for different applied voltages.
- 6 Right-click ID Plot Group 3 and choose Rename.
- 7 In the **Rename ID Plot Group** dialog box, type Displacement vs. Applied Voltage in the **New label** text field.
- 8 Click OK.
- 9 In the Displacement vs. Applied Voltage toolbar, click 🗿 Plot.

Add a plot of tip displacement versus applied DC voltage.

ID Plot Group 4

In the Home toolbar, click 📠 Add Plot Group and choose ID Plot Group.

Point Graph 1

- I Right-click ID Plot Group 4 and choose Point Graph.
- **2** Select Point 12 only.
- 3 In the Settings window for Point Graph, click Replace Expression in the upper-right corner of the y-Axis Data section. From the menu, choose Component I (compl)> Solid Mechanics>Displacement>Displacement field m>w Displacement field, Z component.

Tip Displacement vs. Applied Voltage

- I In the Model Builder window, right-click ID Plot Group 4 and choose Rename.
- 2 In the **Rename ID Plot Group** dialog box, type Tip Displacement vs. Applied Voltage in the **New label** text field.
- 3 Click OK.

4 In the **Tip Displacement vs. Applied Voltage** toolbar, click **O** Plot.

Finally, plot the DC capacitance of the device versus voltage.

ID Plot Group 5

In the Home toolbar, click 📠 Add Plot Group and choose ID Plot Group.

Global I

- I Right-click ID Plot Group 5 and choose Global.
- In the Settings window for Global, click Replace Expression in the upper-right corner of the y-Axis Data section. From the menu, choose Component I (compl)>Electrostatics> Terminals>es.Cll Maxwell capacitance F.

Modify the automatically generated expression to account for the symmetry boundary condition.

3 Locate the y-Axis Data section. In the table, enter the following settings:

Expression	Unit	Description	
2*es.C11	fF	Capacitance	

DC C-V Curve

- I In the Model Builder window, right-click ID Plot Group 5 and choose Rename.
- 2 In the Rename ID Plot Group dialog box, type DC C-V Curve in the New label text field.
- 3 Click OK.
- 4 In the DC C-V Curve toolbar, click **I** Plot.